TOPPAN PHOTOMASK



AR Glass

"If YOU can imagine it, WE can **image** it"



Bio Chip



Bríd Connolly , Andreas Frangen

Holography

Toppan Photomask Co., Ltd. (TPC)

The world's premier provider of photomasks for semiconductors

April 1st, 2022

Teruo Ninomiya

Company Name	Toppan Photomask Co., Ltd.

Location

HQ Tokyo

- Business start
- President
- Shareholders

Toppan Inc. 50.1% Integral Corporation 49.9%

- Headcount 1,800 (as of April 1st, 2022)
- Locations
 8 manufacturing facilities in key geographical locations









Nano Imprint Lithography master Imprint Lithography

DUV reticle/photomask Transmissive Mask Lithography EUV Mask Reflective Mask Lithography

NSAMOTOMASK.

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Photomasks and NIL Masters

- Quartz-etched patterns are also used for projection lithography photomasks
- \rightarrow Same technology used to manufacture NIL masters



Multi-level gratings (e.g. NIL master for AR glasses)

Deep-etch Ouartz

gratings

(e.g. laser applications)







NIL Master Requirements

AR/VR Devices



B.C. Kress, I. Chatterjee "Waveguide combiners for mixed reality headsets" de Gruyter, Nanophotonics 10/2021

Consist of gratings that require:

- L/S gratings of arbitrary orientations
- Precise accuracy of orientation angle
- Minimal periodic placement errors
- Non-vertical Grating profiles
- Various etch depths within one grating

Metalens-based Optics EVG Nanoimprint Lithography | Metalenses - Process Results WD = 3.6 mMag = 1.77 K >

- High resolution
- Meta-atoms of arbitrary shapes and orientations

\rightarrow Our applied Photomask technology is the enabler of these new segments!

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Staircase Gratings & 3D Pattern



ullet

- Staircase is an option for non vertical profiles
 - discrete steps of various widths and depths





3D pattern for other optical applications





Preliminary samples

Slanted Gratings

• AR/VR Gratings typically require non-vertical profiles



15°35°45°Depth:
~150nmImage: Comparison of the second of the se

150nm 1:1 Lines/Space (HM still on top)

Varying Etch Depth





150nm 1:1 Lines/Spaces (HM still on top)

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Meta-atoms of arbitrary Shapes

- NIL masters with meta-atoms of arbitrary shapes at high resolution can be manufactured
- NanoImprint can accurately reproduce these shapes by EVG tools





Joint White Paper Toppan & EVG illustrates availability of processes/tools for high-volume manufacturing of metalenses using NIL

Summary

→ Photomask technology is well suited to manufacture NIL masters for advanced optical devices

Our Offer:

- Industrialized setup for prototypes and high-volume manufacturing of masters
- Excellent understanding & implementation of special requirements of NIL masters
- Access to high production and e-beam capacity
- Tightly controlled manufacturing processes and defect-free environment
- 6" square Quartz and 8" round Silicon form factors





TOPPAN PHOTOMASK

Toppan's industrialized, state of the art technology will bring Your cutting-edge products into reality

We look forward to a Bright Future with you

For more information, please contact us https://www.photomask.co.jp Email: photomask@toppan.co.jp